

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Schaepkens et al.

Application No.: New Application

Filed: Herewith

For: REPLACEABLE PLATE EXPANDED THERMAL PLASMA APPARATUS
AND METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

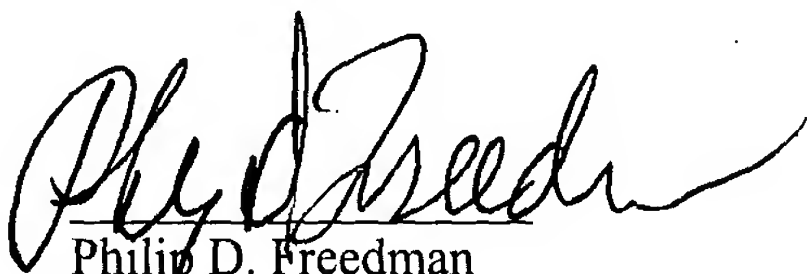
Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached Form PTO-1449. One copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

No fee should be required. However, please credit or debit Deposit Account No. 500917 as needed to ensure consideration of the disclosed information. Two copies of this paper are attached.

Respectfully submitted,



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Form PTO-1449 US Dept. of Commerce (REV. 8-83) PATENT & TRADEMARK OFFICE				ATTY DOCKET .136086-1		APPLICATION NO.	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT Schaepkens et al.			
				FILING DATE		GROUP	

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLAS S	FILING DATE IF APPROPRI- ATE
		2003/0072881	4/2003	Yang et al.			
		2002/0050323	5/2002	Moisan et al.			
		2001/0022295	9/2001	Hwang			
		6,426,125	7/2002	Yang et al.			
		6,397,776	6/2002	Yang et al.			
		6,365,016	4/2002	Iacovangelo et al.			
		6,213,049	4/2001	Yang			
		6,110,544	8/2000	Yang et al.			
		4,871,580	10/89	Schram et al.			

FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLAS S	TRANSLATION	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)			
			van 'de Sanden et al., The expanding thermal arc plasma: the low-flow regime, Plasma Sources Sci. Technol., 7, pp. 28-35 (1998)

EXAMINER	DATE CONSIDERED
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Examiner:	Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.
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